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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			
<b>PRELIMINARY AMENDMENT</b>		Docket Number: <b>01662/54902</b>	
Application Number (Express Mail No. EL244508891US)	Filing Date October 19, 2001 <b>10045510</b>	Examiner	Art Unit
Invention Title <b>CRYSTALLINE VENLAFAXINE BASE AND NOVEL POLYMORPHS OF VENLAFAXINE HYDROCHLORIDE, PROCESSES FOR PREPARING THEREOF</b>		Inventor(s) <b>DOLITZSKY et al.</b>	

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Date: 11/26/01 Reg. No. 46,877

Signature: *Siu K. Lo*  
Siu K. Lo

SIR:

Prior to examination, please amend the above-referenced patent application as follows:

In the Claims

Please add the following new claims 76-80:

- a1*  
*SUB*  
*B1*
- 76. (New) A process for preparing venlafaxine hydrochloride Form I comprising the steps of:  
a) preparing a mixture of venlafaxine in isopropanol; and  
b) exposing the mixture in gaseous hydrochloric acid at pH 7.
77. (New) The process according to claim 76, wherein the exposing step is carried out at about 20°C.
78. (New) The process according to claim 76, further comprising the step of crystallizing venlafaxine hydrochloride Form I by heating followed by cooling the mixture.
79. (New) The process according to claim 78, wherein the mixture is heated to form a clear solution.

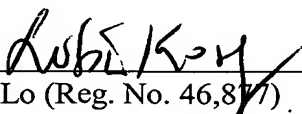
80.

(New) The process according to claim 78, wherein the mixture is cooled gradually to about 10°C.--

Support for these new claims can be found in the specification; for example, p.17, lines 19-25  
(example 16).

Dated: 11/26/01

Respectfully submitted,

  
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